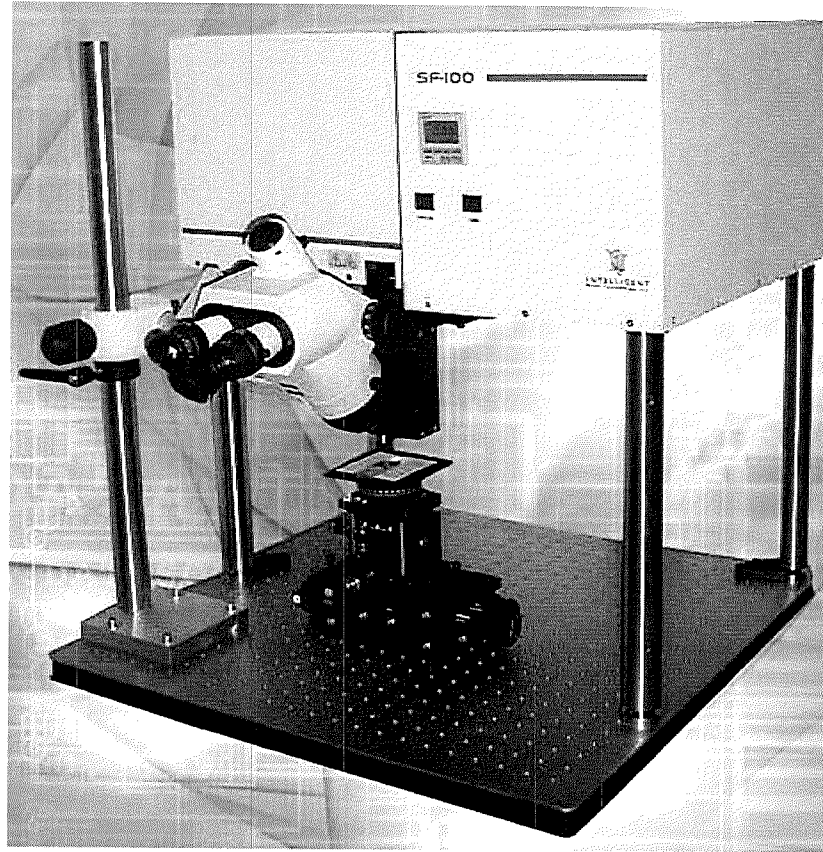


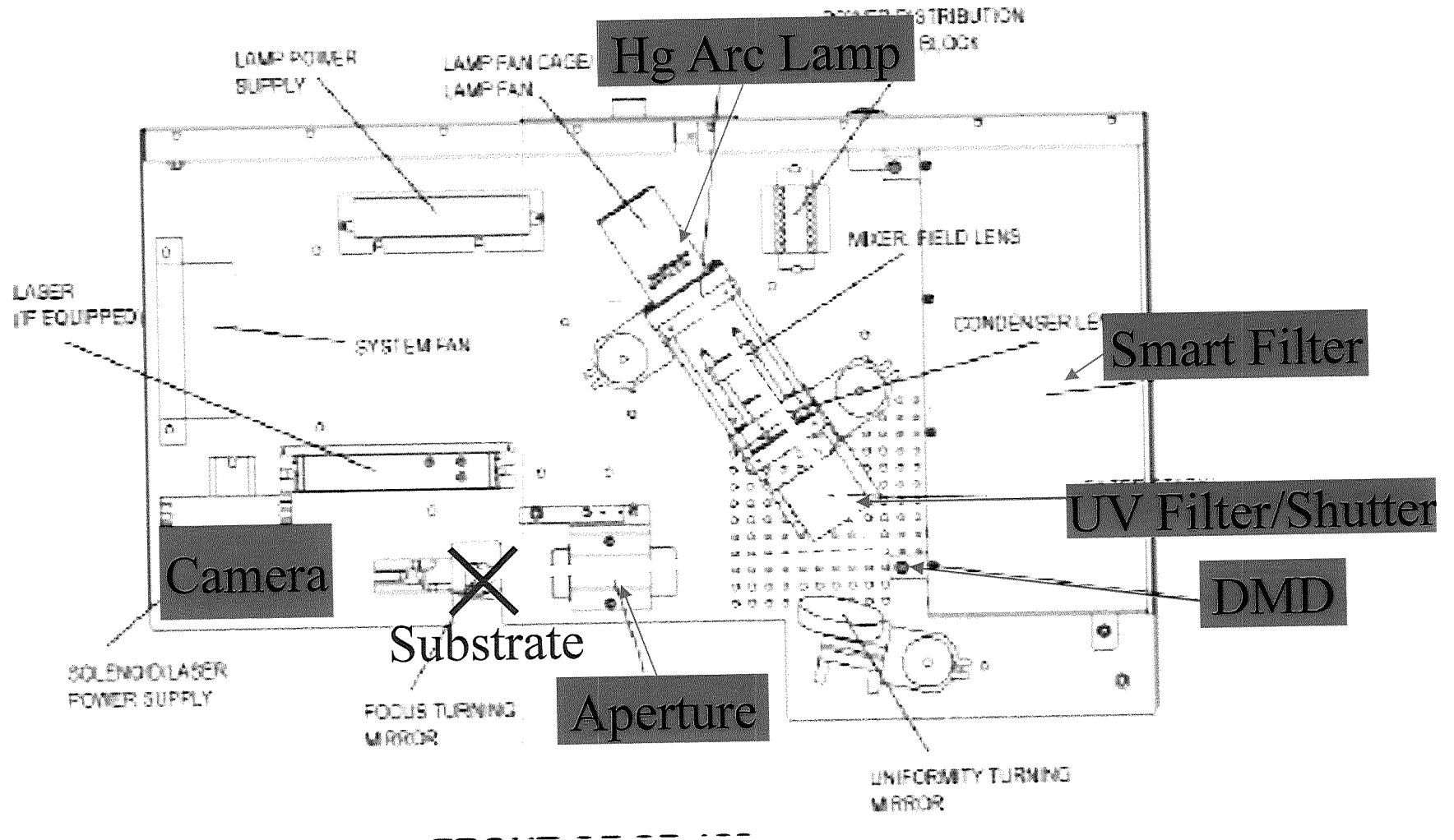
# SF-100 Exposure System

## Intelligent Micro Patterning



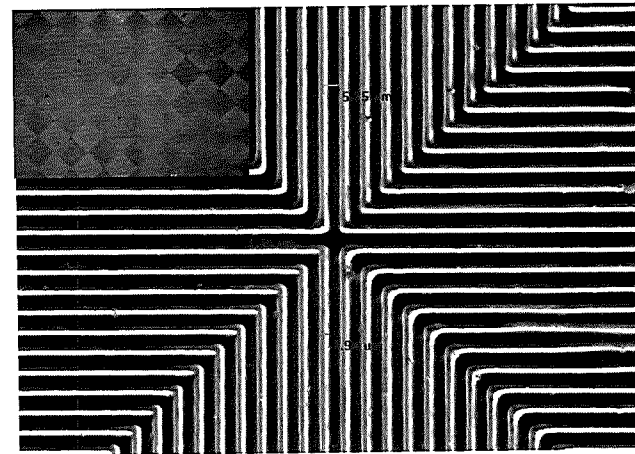
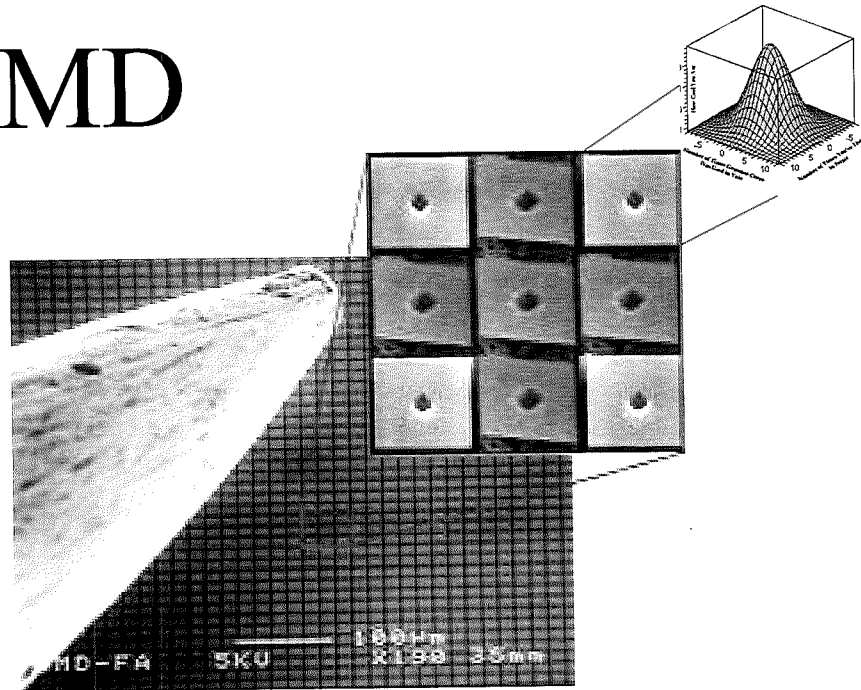
Maskless Patterning System

# The Guts



# The DMD

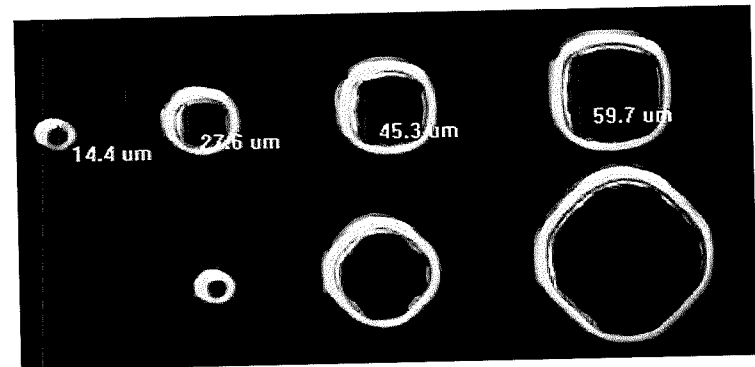
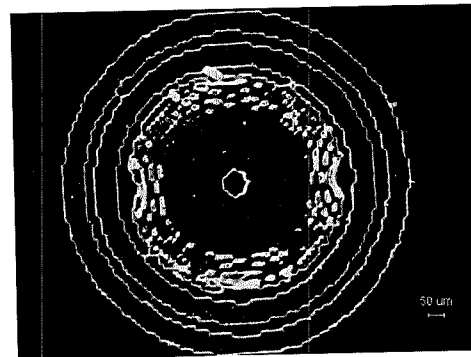
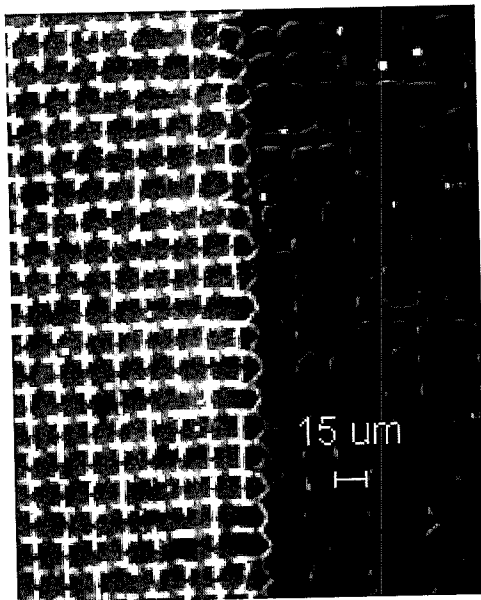
- Micromirror array used to generate image for maskless lithography
  - 1 cm X 1.5 cm exposure area
    - Stepper motor controlled autostage ‘stitches’ larger exposure areas together
      - Overlap areas greyscaled
  - Mirrors 13.75  $\mu\text{m}$  square  $\rightarrow$   $\sim 15 \mu\text{m}$  minimum feature size
    - 3x reduction optics yields approx minimum resolution/features of 5  $\mu\text{m}$
  - Energy reflected from a mirror has a gaussian distribution
    - ‘ghosting’ algorithm can be used to correct for this
  - Aperture reduces light intensity by 5X, improves sidewall fidelity, limits gaussian energy distribution  $\rightarrow$  decreases scalloping



*2 cm X 3 cm SU-8 field and magnified area demonstrating 5  $\mu\text{m}$  features*

# Consequences of the DMD

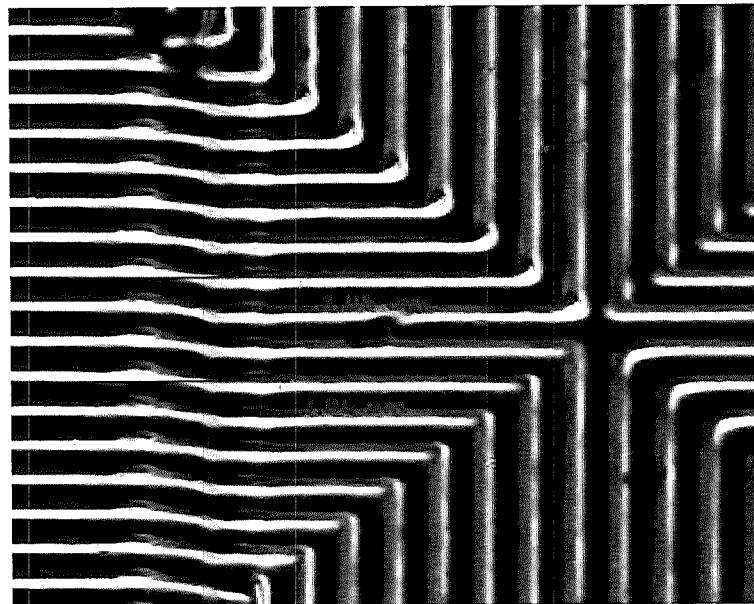
- Exposure performed in pixels
  - Bitmap files required
  - All features must be multiples of the minimum feature size ( $\sim 5$  or  $15 \mu\text{m}$ )
  - Curves are composed of segments



*Mirror geometry evident if under-exposed, curves 'pixelated', multiples of min feature, circles approximated*

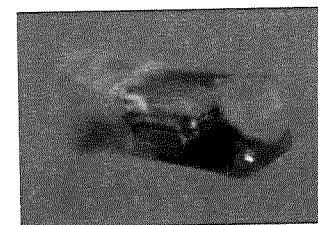
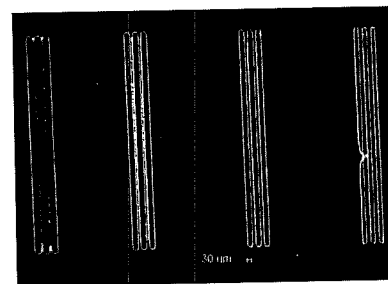
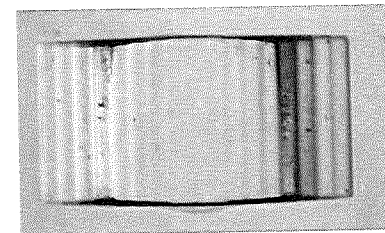
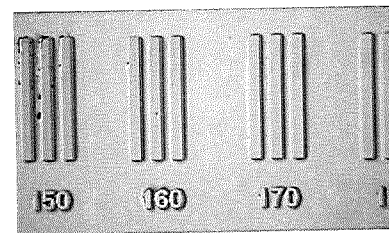
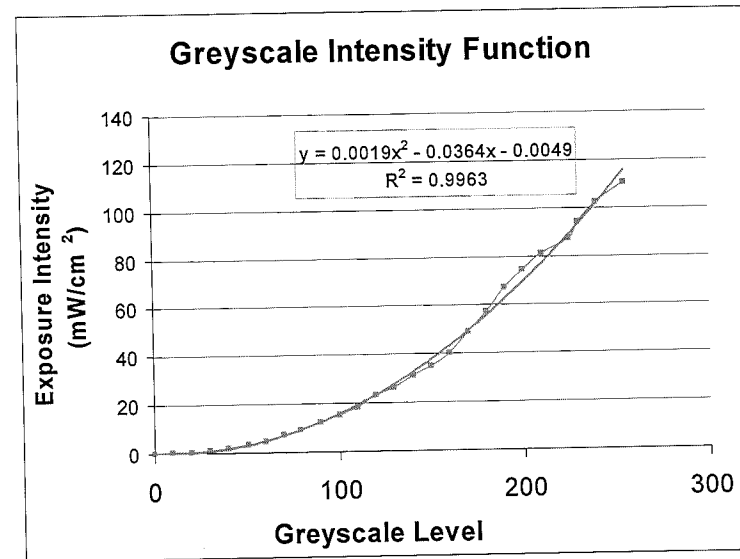
# Stitching

- Exposure fields larger than the exposure area (1.5 cm X 1 cm) are stitched together
  - Areas of overlap are greyscaled so that they receive approx. the same exposure energy
    - doesn't add up due to additional activation energies
  - Accuracy  $\pm 2.5 \mu\text{m}$  (best, Random error)
    - Relative error increases with decreasing feature size



# Greyscale

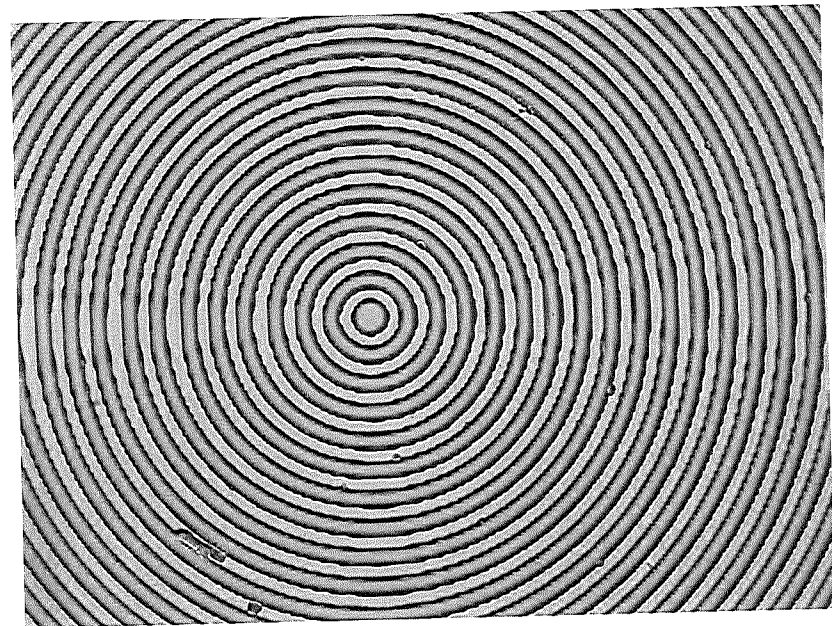
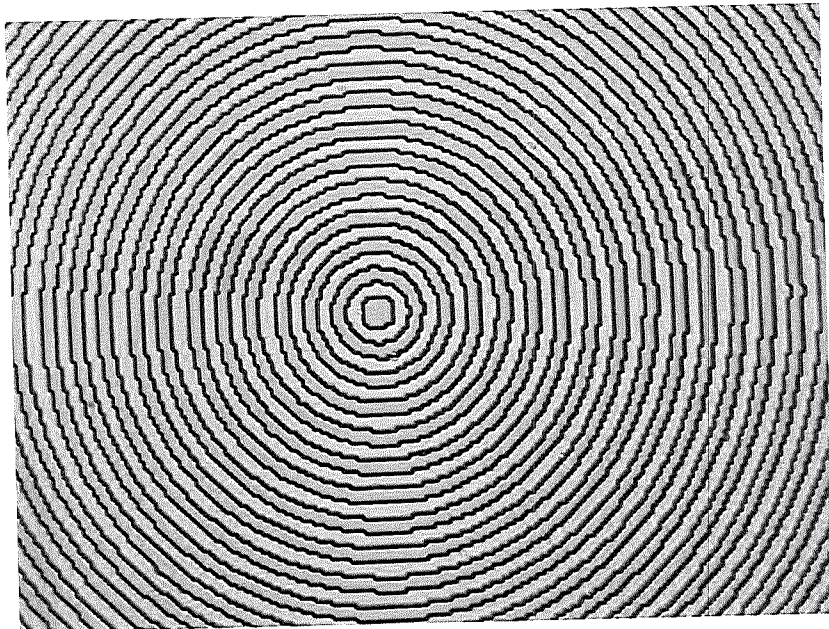
- 0-255 levels of Greyscale
- Mirrors are modulated to reduce energy
- Non-linear response
  - (note greyscale values used in stitching)
- Useful for rapidly determining ~ exposure time
- Can be used to generate 3D topography



*Using greyscale to evaluate different energies effect on resolution and adhesion. Use of greyscale to generate 3D topography.*

# Greyscale for reducing pixelation

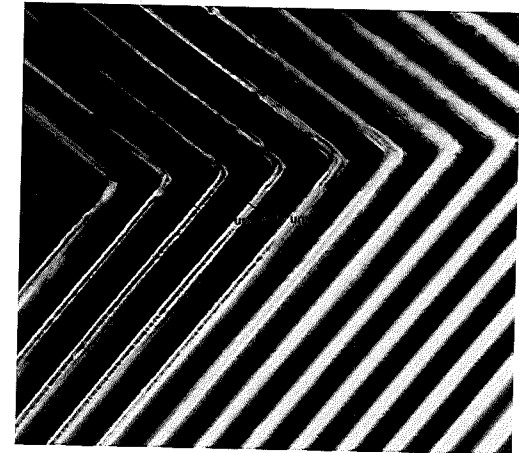
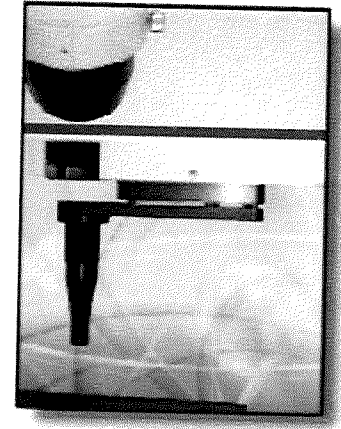
- Many design programs have an anti-aliasing algorithm that uses greyscale to make curves appear smoother
- Works to generate smoother curved features



*Exposure of Monochrome Bitmap vs. greyscale bitmap with anti-aliasing*

# Reduction Optics

- 1/3X reduction optics reduces minimum feature size to 5  $\mu\text{m}$ 
  - Reduces exposure area by factor of 9
  - Can reduce apparent pixelation: 9:1
  - Easily inserted and removed
    - Must refocus image
  - Stitching with reduction optics
    - Error significant for reduced features
    - Can use multilayer alignment program to include ‘islands’ of small features in a field of larger features

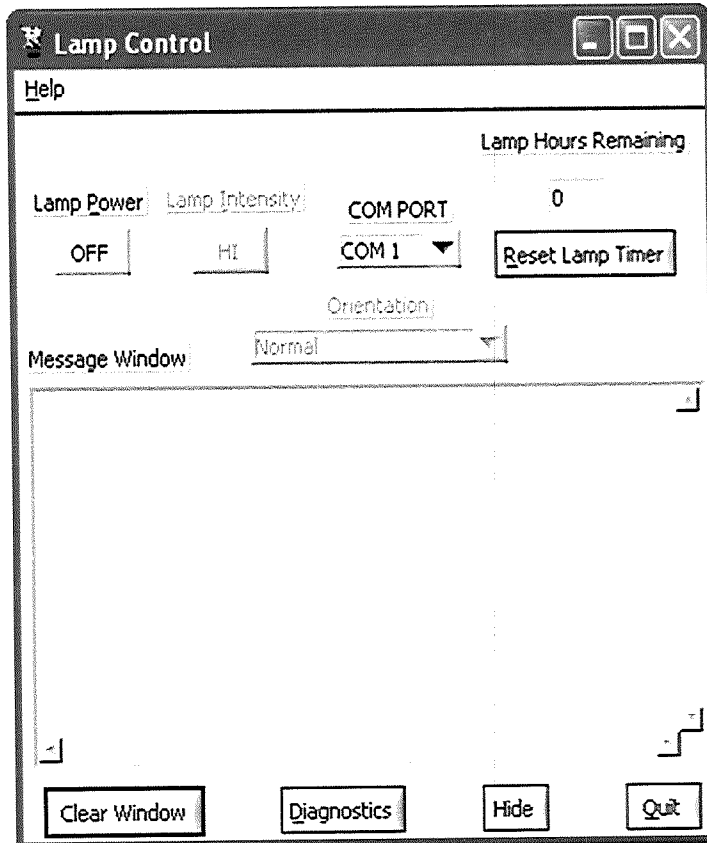




# Using the Tool: Turn on Sequence

- Ensure computer is booted up
- Turn on SF-100 with switch at rear of tool
- Turn on Stage Controller
  - If the sequence is not followed, or the computer fails the autostage may move erratically and need to be turned off
- Turn on Lamp (*wait warming up for > 15 min*)
- Turn system off in reverse order
  - Allow lamp to cool before turning off SF-100
  - Best to check the air exiting the left of the tool to ensure complete cooling

# Using the Tool: The Lamp

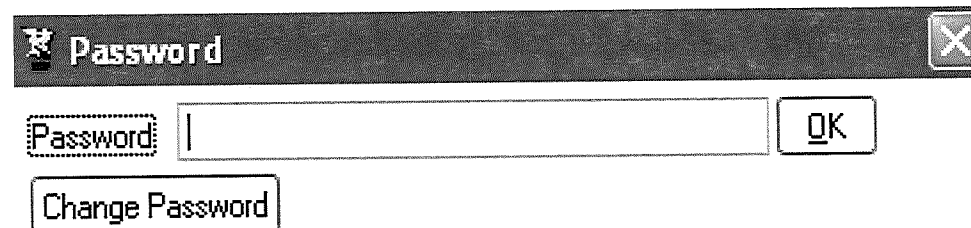


- Intensity  $\sim 20$  mW/cm<sup>2</sup>
- Separate Program
- Pressing button under “Lamp Power” turns lamp on/off, text displays status
- “Low” Intensity is 90%
- Com Port 1
- Dialogue window for actions/errors

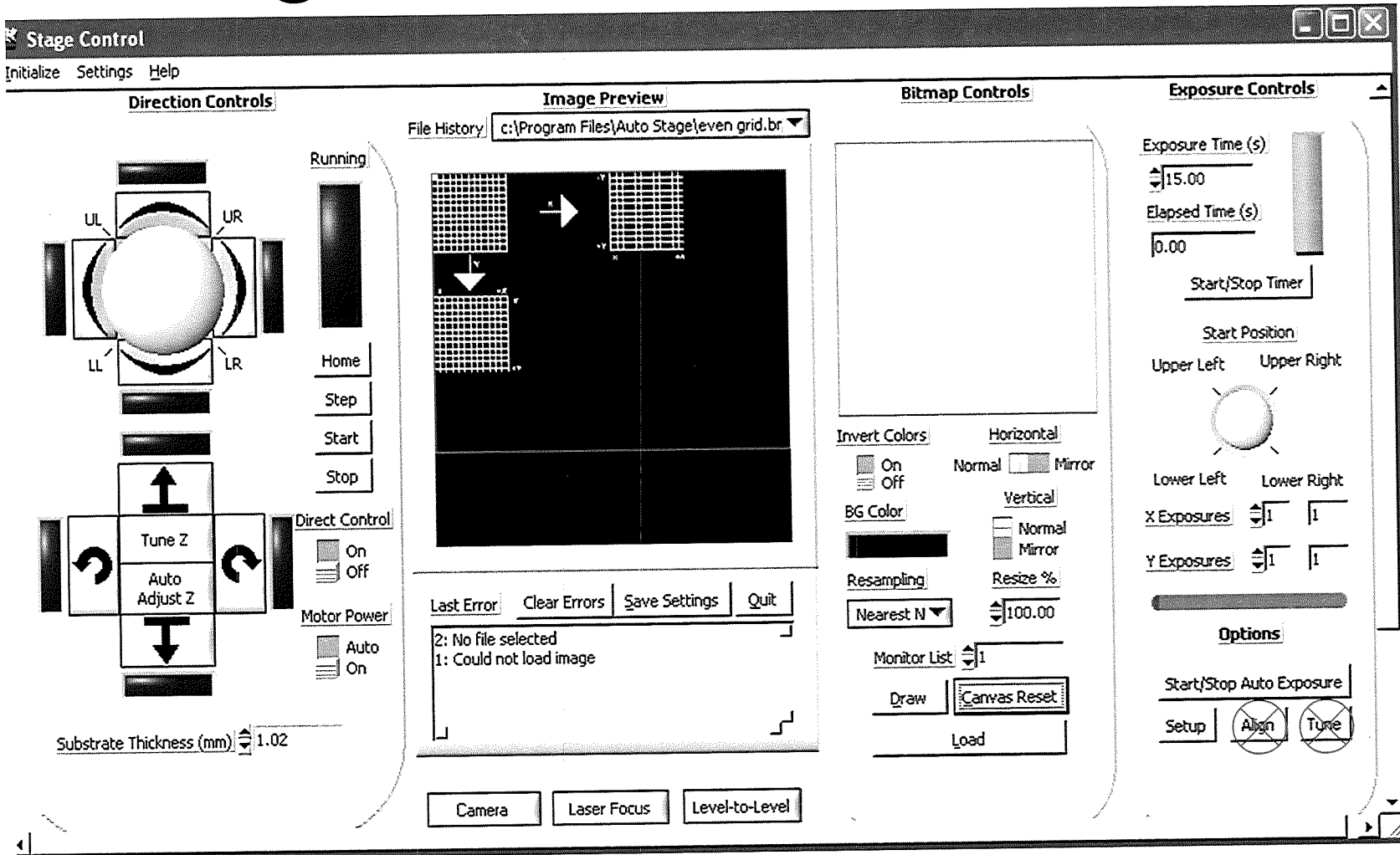
- Allow lamp to warm up 15-30 min
- Allow lamp to cool before turning off system
- Please do not reset the timer or change the orientation
- Please notify if timer is near 0 Hours

# Using the Tool: Autostage Basic

- Password for some advanced control
  - Stage speed, exposure window control, maintenance/alignment
- Click OK without enetering to use basic autostage program
- Password can be obtained if necessary



# Using the Tool: Autostage Basic



Stage control

Auto Focus

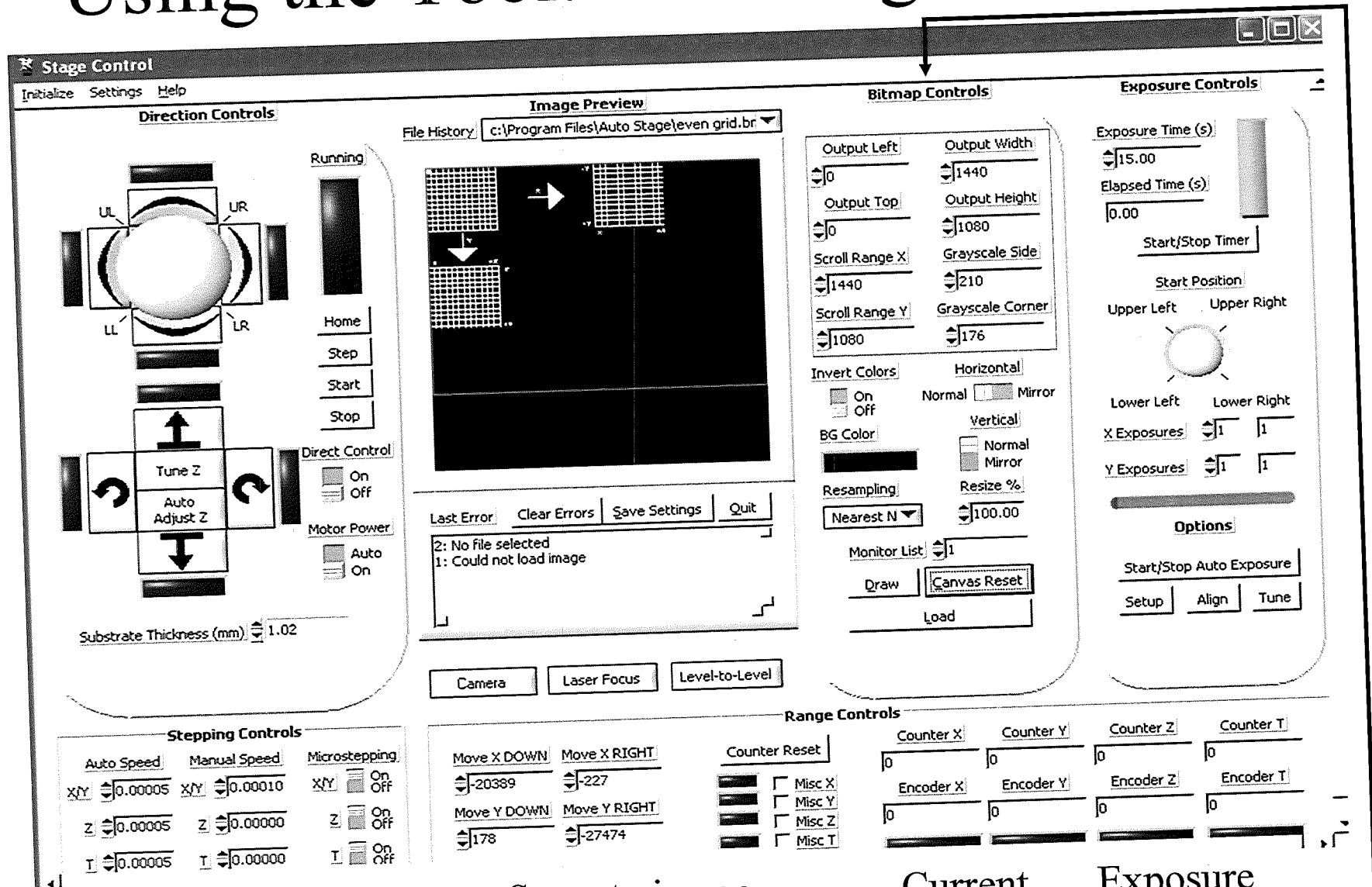
Image control window

Links to advanced options

Exposure

12  
Stitching

# Using the Tool: Autostage Advanced



Stage speed delay value

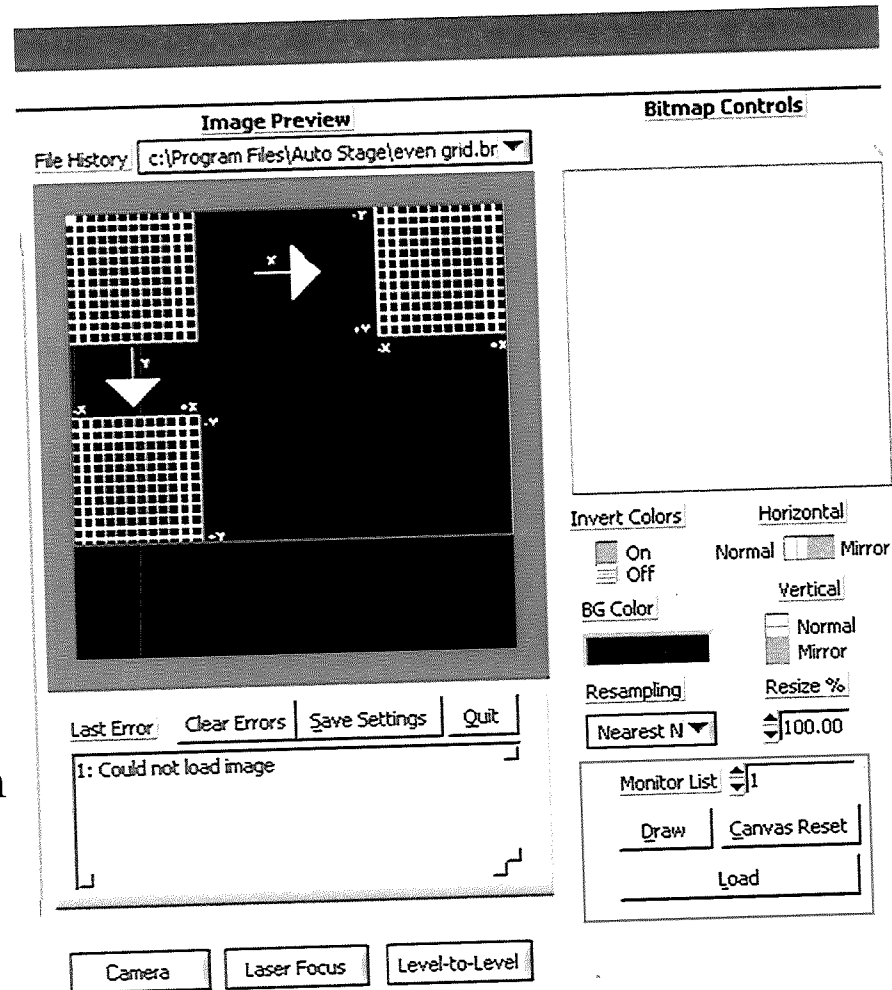
Stage to image alignment encoder values

Current encoder values

Exposure window controls

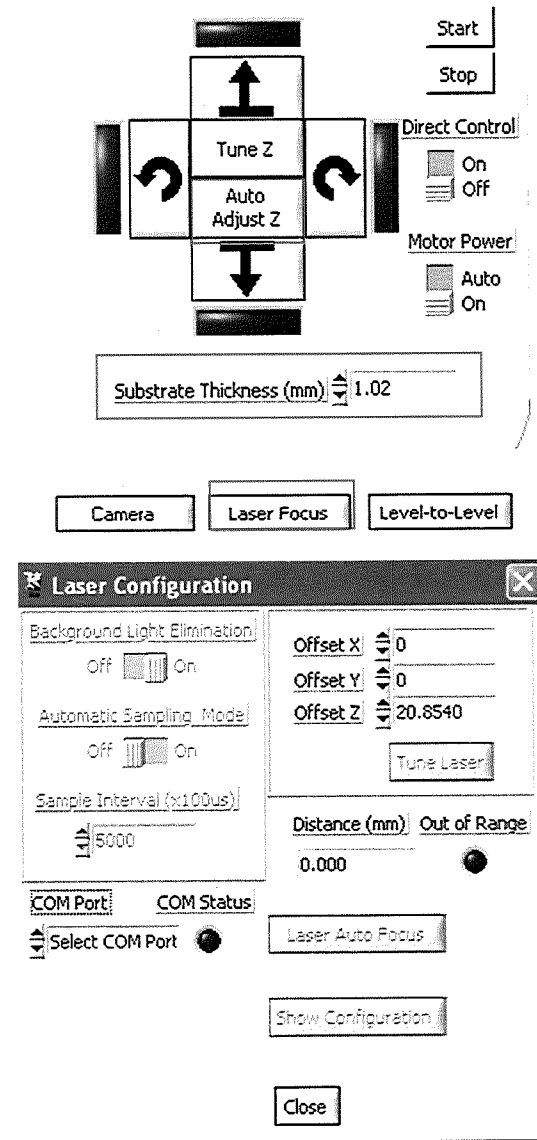
# Using the Tool Step 1: Loading the Image

- Once the lamp is warmed up and the Autostage program has been opened...
  - Load your image
    - Not from desktop!
  - Perform canvas reset
  - Draw to monitor 1 to check artwork
  - Draw to monitor 2 to load image into Smartfilter
    - UV Filtered Green Image
    - Clicking on the image preview will highlight the area and allow the arrow keys to be used to toggle through different portions of a large field design
  - Optics horizontally mirror image and then rotate it 90°
  - Other tools for quick image manipulation
    - Resampling algorithms for resizing
      - Resize up to 200%



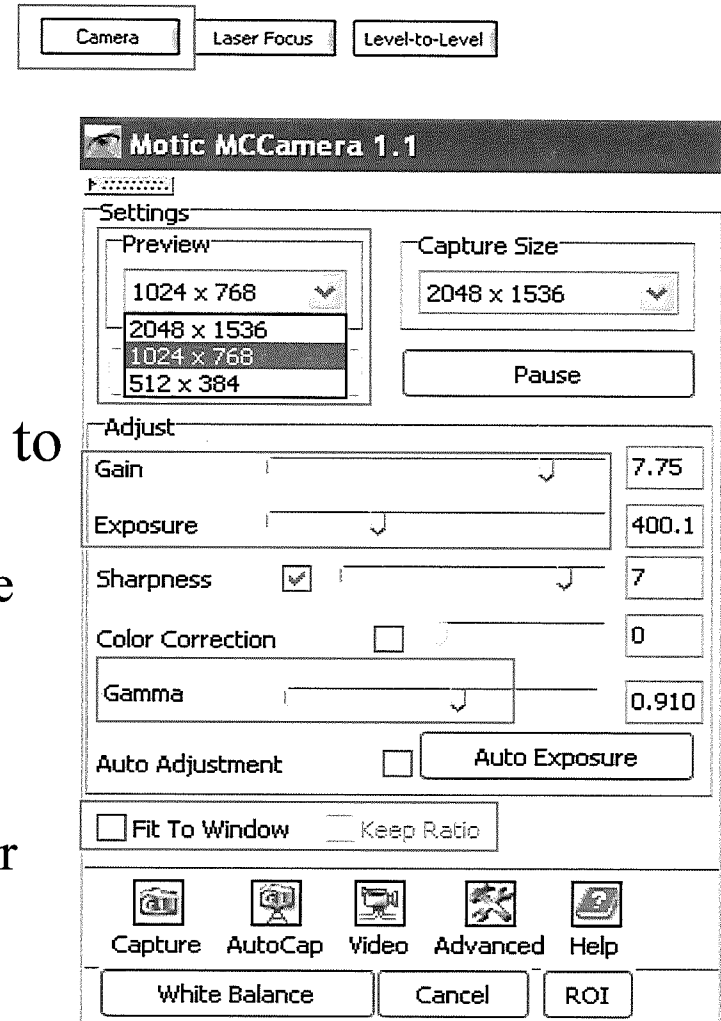
# Using the Tool Step 2: Focusing the Image

- Auto Z
  - Image focused manually by tech during setup
  - Entering substrate thickness +  $\frac{1}{2}$  resist thickness and hitting “Auto Adjust Z” autofocuses
- Laser Focus
  - Uses laser to Autofocus image
  - Follow “Tune Laser” Steps
  - Miscalculates on reflective or transparent substrates
  - Sometimes useful to measure distances
  - Enter this menu to turn laser off, Comport 4, hit comport again to get loading box to go away
- If refocusing is needed (e.g. reduction optics usage) aperture must be removed



# Using the Tool Step 2: Focusing the Image

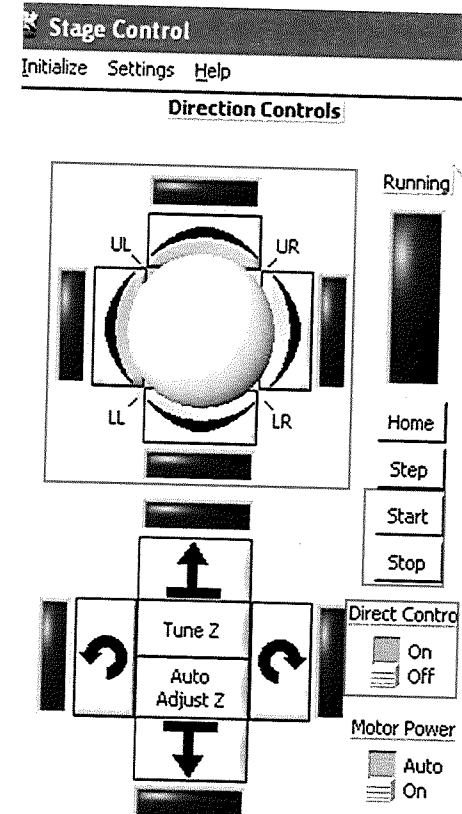
- Can check focus with Motic
  - “Camera” in Autostage opens Motic
  - Generally unnecessary
    - 10  $\mu\text{m}$  change in Z away from focal plane  
→ 0.1 % error in X/Y plane
  - Depending on substrate/resist may need to play with gain/exposure to view image
    - Increased exposure reduces camera response time
    - Gamma ratio can improve contrast
    - Native resolution, can increase
    - Highlight area, Fit to Window, keep ratio for digital zooming
    - Camera 1.5X magnification, can add additional 2X for advanced operations





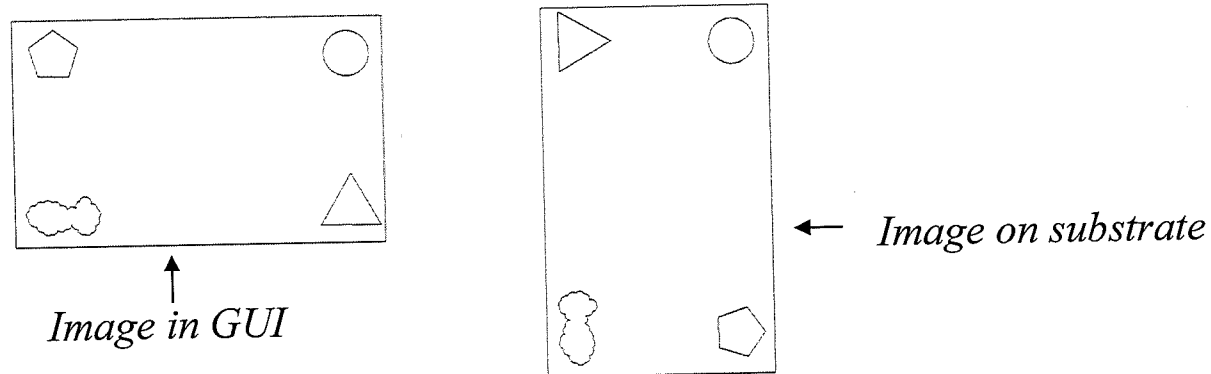
# Using the Tool Step 3: Image-Substrate Relations

- Moving the Stage in X and Y
  - Important to ensure a stitched exposure will not go off substrate
  - To Place image where desired on substrate
- Vacuum chuck available
- Toggle “Direct Control” on to use Joystick, PGM control, or Arrow keys
  - Keep in mind the stage moves not the image
  - Directions can be chosen (will highlight on PGM) then “Start” & “Stop” to control stage
  - Alternatively Stage can be started and directions can be changed on the fly
  - Yellow highlight indicates stage has hit a limit
  - Shift and Home, End, arrow keys: start, stop and move the stage



# Using the Tool Step 3: Image-Substrate Relations

- Image is horizontally mirrored and rotated clockwise 90°



- Moving a single exposure window (scroll range) is useful for multiple exposures of the same image, aligning substrate for stitching, and determining image fit
  - Choose direction
  - For single scroll range directions are mirrored and rotated 90° (directions do not directly translate only for this application!!!)
  - Arrow Key map: →, moves away; ←, moves towards; ↑ moves right; ↓ moves left
  - Advanced controls allow scroll range to be changed

# Using the Tool: Joystick

- To use the Joystick for Autostage control Open the logitech profiler with the W icon near the clock
- Useful when performing gross alignment
- Select “Play Stage” to open the Autostage program

**Up:** Rotate Lever Forward to select direction

**Down:** Rotate Lever Backward to select

**Right:** Move joystick far right to select activate trigger to start motion and again

**Left:** Move joystick far left to select direction

**Forward:** Move joystick away from user direction

**Backward:** Move joystick toward user

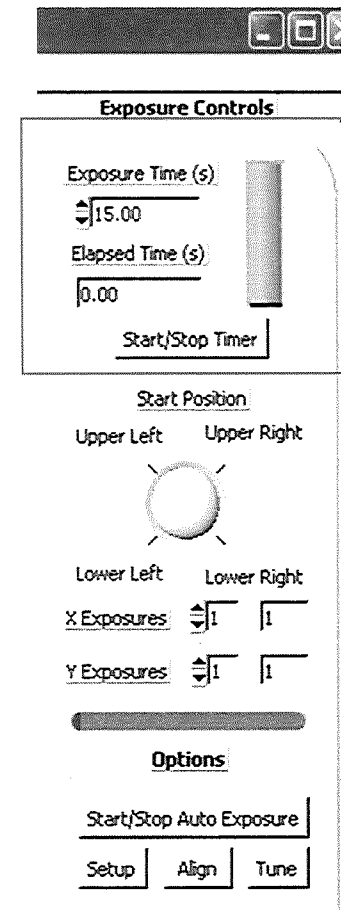
**Rotate Clockwise:** Rotate joystick clockwise direction

**Rotate Counterclockwise:** Rotate joystick counterclockwise to select direction counterclockwise to select direction



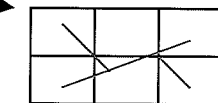
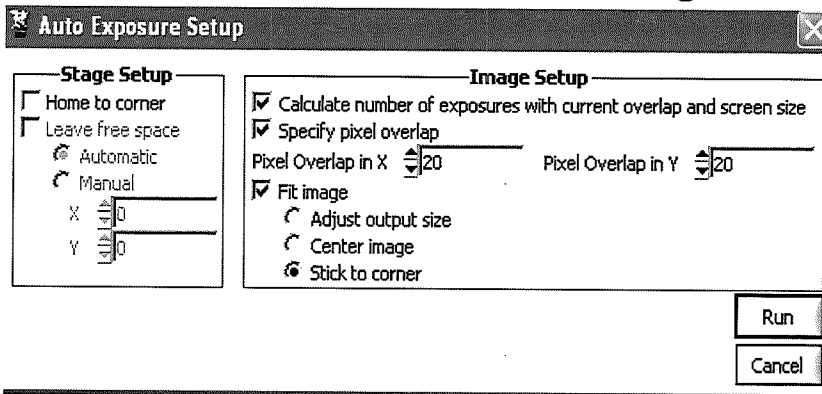
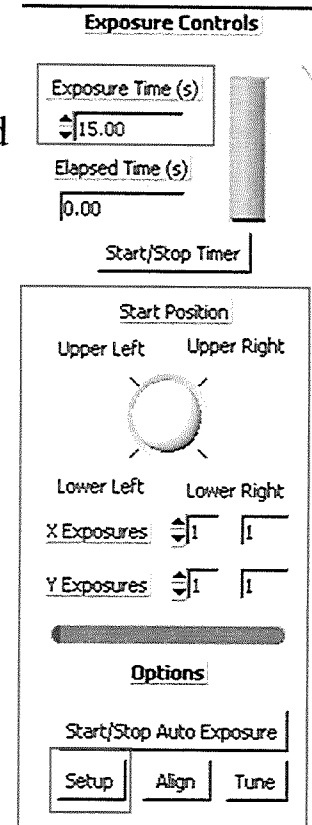
# Using the Tool Step 4: Exposure; Single Shot

- Ensure lamp is warmed up and ‘full of life’
- Set desired exposure time
  - 0.01 s resolution
- Press “Start/Stop Timer” to removed UV filter and start exposure
  - Note that additional time elapses to account for shutter speeds



# Using the Tool Step 4: Exposure; Stitching

- Larger field images are composed of multiple single shots
  - Each shot is overlapped (greyscale at overlap) and the stage moves automatically to exposure entire image
    - Moves in serpentine pattern
    - Greyscale levels controlled in bitmap controls, experimentally optimized
    - Alignment for stitching performed during system setup
- Consider image-substrate relations and check that entire image will fit on substrate/find a starting point.
- Ensure direct control is off
  - Use start position dial to control where exposure starts
  - Run setup:
    - to control exposure window placement relative to image
    - Control pixel overlap (min 4, 20 recommended)
    - Will auto calculate number of X and Y exposures
  - X and Y exposures. Grid based, e.g.



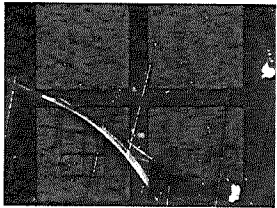
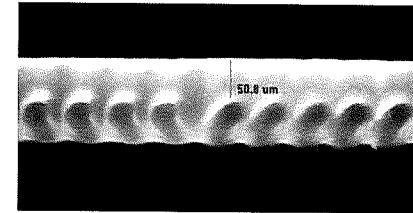
$$X = 3, Y = 2$$

- Input exposure time and hit “Start/Stop Auto Exposure” to start

# Multilayer Lithography

- Level-to-Level alignment Program

- Align image to features on substrate
- Use at least 3 fiduciary marks



- Align image to marks using camera
- Calculates theta offset and scale offset and corrects for them
  - Scale is for features that are not the expected size
- Perform 3 iterations to generate low offset values

**Level-to-Level**

**Alignment Mark Table**

	X Coordinate	Y Coordinate	Scaled X	Scaled Y
Initial	720	540	720	540
Mark 1	0	0	0	0
Mark 2	0	0	0	0
Mark 3	0	0	0	0
Mark 4	0	0	0	0

**Calculated**

X	0
Y	0

**Corrected**

X	0
Y	0

**Offsets**

Theta (degrees)	0.000000
Scale (%)	0.000000

Current Mark: 1

Encoder Resolutions: X: -1000, 1000; Y: 1250, 1250; Z: 1250, 1250; T: 1250, 1250

# Summary for Use

- Load image
- Focus image
- Move substrate to point of exposure/ensure image will fit on substrate
- Expose
  - Determine exposure time
  - Setup stitching parameters
- Link to Manual in Help file of Autostage and on Desktop

*When disconnecting Hardware Please do not disconnect DAQ card accidentally*

